



**PROCESS SOLUTIONS
YOU CAN COUNT ON**

VP SERIES

VACCUM PLASMA TREATMENT SYSTEM

Features & Benefits

- Adjustable shelves allow processing of a wide variety of part geometries.
- Batch style: each unit is completely self-contained, requiring minimal floor space
- Ultra-low temperature: temperature as low as 40°C
- Omni-directional surface cleaning: the anisotropic plasma can enter the ultra-fine slit cleaning
- Environmentally Friendly: No chemicals are used and no harmful substances are produced.
- Cleaning: remove fine dust, oil, grease and organic compounds.
- Activation: Increases surface energy to promote wetting and adhesion.

Product Description

Vacuum plasma is used to etch away a layer of material a few atoms thick during the manufacturing of small integrated circuit chips.

VP series plasma treatment machines are suitable for a wide variety of plasma cleaning, surface activation and adhesion improvement applications.

The VP Series consists of four batch plasma treatment systems each with a different vacuum chamber size. The horizontal electrodes allow for large batch loads.

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Specifications :

System Specifications

VP Series Vacuum Plasma Treatment System

Model no.	VP-60	VP-80	VP-100	VP-150
Dimension	L 1200 × W 920 × H 1690 mm			
Chamber Size	403×400×403mm	450×400×450mm	470×460×470mm	500×600×500mm
Electrode Plate Structure	Horizontal 8 layers			
Vacuum Pump System	Two-stage Rotary Plate Vacuum Pump / Roots Vacuum Pump			
Vacuum Measurement System	Pirani Resistance Vacuum Meter			
Gas Flow Sensor	Mass Flow Controller			
Plasma Generator	500 W			1000 W
Automatic Matching Device	500 W			1000 W
Control System Hardware	PLC Controller with Touch Panel			
Weight	350 KG	400 KG	420 KG	450 KG
Power Supply	AC 380V 3 Phase			
Rated Power	4 KW			4.5 KW
Gas Generator	Two working gases are optional (Ar,N ₂ ,O ₂ ,CF ₄ ,CDA)			
Pressure	0.6 Mpa			